

EDA/CAD FOR NANOELCTRONICS

2020/21

M. Helena Fino

Eda/CAD for Nanoelectronics

- We will start preparing the second evaluation project
- The project will focus on TFTs – Thin Film Transistors
 - ▣ Modeling
 - Model 1
 - Model 2
 - ▣ Parameter extraction
- We will develop our work using measurements on devices implemented at the Materials Department

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□ Model 1

$$I_D = \begin{cases} 0 & \leftarrow V_{gs} < V_t \\ \mu_{ef} C_i \frac{W}{L} \left(V_{gs} - V_t - \frac{V_{ds}}{2\alpha} \right) V_{ds} & \leftarrow V_{gs} > V_t \wedge V_{ds} < \alpha(V_{gs} - V_t) \\ \mu_{ef} C_i \frac{W}{L} (V_{gs} - V_t)^2 \left(\frac{\alpha}{2} \right) & \leftarrow V_{gs} > V_t \wedge V_{ds} \geq \alpha(V_{gs} - V_t) \end{cases}$$

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□ Model 1 [1]

$$I_D = \begin{cases} 0 & \leftarrow V_{gs} < V_t \\ \mu_{ef} C_i \frac{W}{L} \left(V_{gs} - V_t - \frac{V_{ds}}{2\alpha} \right) V_{ds} & \leftarrow V_{gs} > V_t \wedge V_{ds} < \alpha(V_{gs} - V_t) \\ \mu_{ef} C_i \frac{W}{L} (V_{gs} - V_t)^2 \left(\frac{\alpha}{2} \right) & \leftarrow V_{gs} > V_t \wedge V_{ds} \geq \alpha(V_{gs} - V_t) \end{cases}$$

$$\mu_{ef} = \mu_0 \left(\frac{V_{gs} - V_t}{V_{AA}} \right)^\gamma$$

[1]P. Servati, D. Strikhilev and A. Nathan, "Above-threshold parameter extraction and modeling for amorphous silicon thin-film transistors," in IEEE Transactions on Electron Devices, vol. 50, no. 11, pp. 2227-2235, Nov. 2003, doi: 10.1109/TED.2003.818156.

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□ Model 1

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$$\mu_{ef} = \mu_0 \left(\frac{V_{gs} - V_t}{V_{AA}} \right)^\gamma$$

$$I_{D_sat} = \mu_0 \frac{C_i}{V_{AA}^\gamma} \frac{W}{L} (V_{gs} - V_t)^{2+\gamma} \left(\frac{\alpha}{2} \right)$$

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□ Model 1

a) Read Measurements files:

1. $I_d(V_{gs})$ in transfer in saturation
2. Plot $I_d(V_{gs})$
3. $I_d(V_{ds})$ output characteristics for several V_{gs}
4. Plot $I_d(V_{ds})$ for several V_{gs}

b) Obtain model parameters K_{sat} , V_t , m , γ , λ ($I_d = I_{D_sat}(1 + \lambda \cdot v_d)$)

$$I_{D_{sat}} = K_{gsat} \frac{W}{L} (V_{gs} - V_t)^m$$

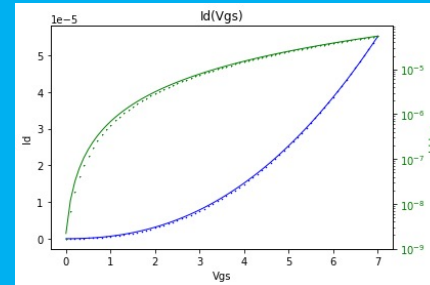
$$I_{D_sat} = \mu_0 \frac{C_i}{V_{AA}^\gamma} \frac{W}{L} (V_{gs} - V_t)^{2+\gamma} \left(\frac{\alpha}{2}\right)$$

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□ Model 1

a) Read Measurements files:

1. $I_d(V_{gs})$ in transfer in saturation
2. Plot $I_d(V_{gs})$
3. $I_d(V_{ds})$ output characteristics
4. Plot $I_d(V_{ds})$ for several V_{gs}



- b) Obtain model parameters K_{sat} , V_t , m , γ ($I_d = I_{D_sat}(V_{gs} - V_t)^m$)
- c) Plot $I_d(V_{gs})$ from the model, against I_d from measurements
- d) Repeat c) in logarithmic scale
- e) Repeat all for $W/L = 50/05; 50/10; 50/20$
- f) Derive conclusions on the scalability of the model

$$I_{D_sat} = \mu_0 \frac{C_i}{V_{AA}^\gamma} \frac{W}{L} (V_{gs} - V_t)^{2+\gamma} \left(\frac{\alpha}{2}\right)$$